Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	88	438/225.ccls. and polysilicon and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:05
L2	86	L1 and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:13
L3	86	L2 and (sio or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:09
L4	62	L2 and ((sio or oxide) with polysilicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 13:50
L5	12	L4 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:13
L6	8	L5 and (trench or groove or hole or via)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 13:38
L7	0	438/593/ccls. and ((sio or oxide) with polysilicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 13:51
L8	267	438/593.ccls. and ((sio or oxide) with polysilicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 13:51

L9	249	438/593.ccls. and ((sio or oxide) with polysilicon) and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 14:11
L10	74	L9 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 14:11
L11	0	("6221715").URPN.	USPAT	OR	OFF	2004/11/17 14:06
L12	0	("6221715").URPN.	USPAT	OR	OFF	2004/11/17 14:07
L13	12	("4095251" | "4160987" | "4997781" | "5180680" | "5488586" | "5595924" | "5622881" | "5691215" | "5767005" | "5960284" | "5981338" | "6008112").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/11/17 14:07
L14	871	438/257.ccls. and ((sio or oxide) with polysilicon) and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:03
L15	299	L14 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:03
L16	253	L15 not L10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:04
L17	1	("6642109").PN.	USPAT; USOCR	OR	OFF	2004/11/17 14:31
L18	1	("20040152251").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/11/17 14:32
L19	173	438/201.ccls. and ((sio or oxide) with polysilicon) and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:03

L20	56	L19 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:03
L21	50	L20 not L10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:04
L22	34	L21 not L16	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:04
L23	425	438/297.ccls. and polysilicon and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:05
L24	420	438/297.ccls. and polysilicon and gate and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:08
L25	393	L24 not L2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:08
L26	365	L25 and (sio or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:06
L27	38	L26 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:07

L28	147	438/439.ccls. and polysilicon and gate and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:13
L29	128	L28 not L2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:08
L30	126	L29 not L27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:08
L31	26	L30 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:09
L32	25	L31 and (sio or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:09
L33	40	438/362.ccls. and polysilicon and gate and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:14
L34	40	L33 and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:14
L35	6	L34 and (cmp or polish or polishing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:13

L36	19	438/367.ccls. and polysilicon and gate and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:14
L37	19	L36 and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:15
L38	0	438/225.ccls. and 438/593.ccls. and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:15
L39	1681	(Locos or fox or sti or isolation) and ((split or divide or divided or gap or spaced or space) near gate) and (@ad<"20021223")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:17
L40	1136	L39 and oxide and polysilicon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/17 15:17